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# INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet 1 of 10

## Complete if Known

|                        |                  |
|------------------------|------------------|
| Application Number     | Not Yet Assigned |
| Filing Date            | Herewith         |
| First Named Inventor   | Jonathan Doan    |
| Art Unit               | Not Yet Assigned |
| Examiner Name          | Not Yet Assigned |
| Attorney Docket Number | P119-US          |

## U.S. PATENT DOCUMENTS

| Examiner<br>Initials | Cite<br>No. <sup>1</sup> | Document Number |                                   | Publication Date<br>MM-DD-YYYY | Name of Patentee or<br>Applicant of Cited Document | Pages, Columns, Lines, Where<br>Relevant Passages or Relevant<br>Figures Appear |
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|                      |                          | Number          | Kind Code <sup>2</sup> (if known) |                                |  |   |
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|                      |                          | Country Code <sup>3</sup> | Number <sup>4</sup> - Kind Code <sup>5</sup> (if known) |                                |  |   |                |
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|   |   |    | First Named Inventor     | Jonathan Doan          |         |
|   |   |    | Art Unit                 | Not Yet Assigned       |         |
|   |   |    | Examiner Name            | Not Yet Assigned       |         |
| Sheet   | 2 | of | 10                       | Attorney Docket Number | P119-US |

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| Examiner<br>Signature |  | Date<br>Considered | 5-16-06 |
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Sheet 3 of 10

## **Complete if Known**

|                        |                  |
|------------------------|------------------|
| Application Number     | Not Yet Assigned |
| Filing Date            | Herewith         |
| First Named Inventor   | Jonathan Doan    |
| Art Unit               | Not Yet Assigned |
| Examiner Name          | Not Yet Assigned |
| Attorney Docket Number | P119-US          |

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|   |                        | Art Unit                 | Not Yet Assigned |
|   |                        | Examiner Name            | Not Yet Assigned |
| Sheet 4 of 10   | Attorney Docket Number | P119-US                  |                  |

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| Sheet   | 5 | of | 10                       |                  |

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|   | DH                       | IBBOTSON et al., "Comparison of XeF2 and F-atom Reactions with Si and SiO2", Applied Physics Letter, Vol. 44, 1129 (1984).   |                |
|   | DI                       | STRELLER et al., "Selectivity in Dry Etching of Si (100) and XeF2 and VUV Light", Elsevier Science B.V., Applied Surface Science Vol. 106 (1996), pp. 341-346.   |                |
|   | DJ                       | VUGTS et al., "Si/XeF2 Etching: Temperature Dependence", J. Vac. Sci. Technol. A 14(5) (Sep/Oct 1996), pp. 2766-2774.  |                |
|   | DK                       | Y.K. Fang, et al., The Compatibility of Aluminum Layers on Plasma-Deposited W and WSi2 Films, , 1988 IEEE, IEEE Transactions on Electron Devices, Vol. 35, No. 5, May 1988.  |                |

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|   |   |    |                          | Group Art Unit         | Not Yet Assigned |
|   |   |    |                          | Examiner Name          | Not Yet Assigned |
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|  | DL   | WINTERS, H.F., "Etch Products from the Reaction of XeF <sub>2</sub> with SiO <sub>2</sub> , SiO <sub>3</sub> , Si <sub>3</sub> N <sub>4</sub> , SiC, and Si in the Presence of Ion Bombardment", J. Vac. Sci. Technol. B 1(4) (Oct/Dec 1983), pp. 927-931.     |                |
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|   | BA                    | ANDERSON, H.M., "Plasma Diagnostics for Semiconductor Processing", 2000 Digest of the LEOS Topical Meetings (July 24 - 28, 2000), pp. 117-118 (abstract only).   |                |
|   | BB                    | BARYSHEV et al., "Monitoring of $\text{SiO}_2/\text{Si}$ Plasma Etching and End-Point Detection", Mikroelektronika (Russia), Vol. 25, No. 5 (Sep/Oct 1996), pp. 373-379 (abstract only).   |                |
|   | BC                    | BASSOM et al., "Modeling and Optimizing $\text{XeF}_2$ -enhanced FIB Milling of Silicon", 25th International Symposium for Testing and Failure Analysis, Santa Clara, CA (Nov. 14 -18, 1999), pp. 255-261 (abstract only).   |                |
|   | BD                    | BERG et al., "Real-Time Control of Etching Processes: Experimental Results", Proceedings of the SPIE - The International Society for Optical Engineering, Vol. 3213 (1997), pp. 249-260 (abstract only).   |                |
|   | BE                    | CHAMBERS et al., "Endpoint Uniformity Sensing and Analysis in Silicon Dioxide Plasma Etching Using In Situ Mass Spectrometry", J. Vac. Sci. Technol. B, Microelectron. Nanometer Struct., Vol. 16, No. 6 (Nov/Dec 1998), pp. 2996-3002 (abstract only).                            |                |
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|   | BG                    | CHANG et al., "Gas-Phase Silicon Micromachining with Silicon Difluoride", Proceedings of the SPIE - The International Society for Optical Engineering, Vol. 2641 (1995), pp. 117-128 (abstract only).  |                |
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|  | BL                    | LI et al., "Mass Spectrometric Measurements on Inductively Coupled Fluorocarbon Plasmas: Positive Ions, Radicals and Endpoint Detection", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 17, No. 5 (Sept. 1997), pp. 2438-2446 (abstract only).   |                |
|  | BM                    | LIAMANOND et al., "Production Data Based Optimal Etch Time Control Design for a Reactive Ion Etching Process", IEEE Trans. Semicond. Manuf., Vol. 12, No. 1 (Feb. 1999), pp. 139-147 (abstract only).  |                |
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|  | BS                    | PERRIN, J., "Mass Spectrometry of Reactive Plasmas", Plasma Processing of Semiconductors, Chateau de Bonas, France (June 17 - 28, 1996), pp. 397-431 (abstract only).  |                |
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|   | BW   | SEBEL et al., "Reaction Layer Dynamics in Ion-Assisted Si/XeF2 Etching: Temperature Dependence", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 18, No. 6, (Nov. 2000), pp. 2759-2769 (abstract only).  |                |
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|   | CA   | THOMAS et al., "Minimized Response Time of Optical Emission and Mass Spectrometric Signals for Optimized Endpoint Detection", J. Vac. Sci. Technol. B, Microelectron. Nanometer Struct., Vol. 14, No. 4 (July/Aug 1996), pp. 2531-2536 (abstract only).        |                |
|   | CB   | TODA et al., "Thin Beam Bulk Micromachining Based on RIE and Xenon Difluoride Silicon Etching", International Solid State Sensors and Actuators Conference (Transducers '97), Chicago, IL, Vol. 1 (June 16 - 19, 1997), pp. 671-674.                           |                |
|   | CC   | VUGTS et al., "Si/XeF2 Etching: Reaction Layer Dynamics and Surface Roughening", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 14, No. 5 (Sept/Oct 1996), pp. 2780-2789 (abstract only).   |                |
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|   | CE   | WAN et al., "Electron Cyclotron Resonance Plasma Reactor for SiO2 Etching: Process Diagnostics, End-Point Detection, and Surface Characterization", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 13, No. 4 (July/Aug 1995), pp. 2035-2043 (abstract only).  |                |
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| CG  | WARD, P.P., "Plasma Process Control with Optical Emission Spectroscopy", 17th IEEE/CPMT International Electronics Manufacturing Technology Symposium: Manufacturing Technologies - Present and Future, Austin, TX (Oct. 2 - 4, 1995), pp. 166-169 (abstract only). |  |                |

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|   | CH                    | WARNEKE, et al., "In Situ Characterization of CMOS Post-Process Micromachining", Sens. Actuators A, Phys. (Switzerland), Vol. A89, No. 1-2 (March 20, 2001), pp. 142-151 (abstract only).   |                |
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|   | CJ                    | WODECKI, N.D., Low Open Area Multi-Layered Dielectric Film Etch Endpoint Detection Using EndPoint Plus (TM)", Proceedings of the SPIE - The International Society for Optical Engineering, Vol. 3882 (1999), pp. 231-238 (abstract only).                       |                |
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|   |   | Filing Date              | 3/18/04          |                        |         |
|   |   | First Named Inventor     | Doan             |                        |         |
|   |   | Art Unit                 | 1765             |                        |         |
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|                       |               | US- 3.511.727                  | 05-12-1970                     | Hays, R.G.   |   |
|                       |               | US- 4.190.488                  | 02-26-1980                     | Winters, H.F.                                      |   |
|                       |               | US- 4.310.380                  | 12-12-1982                     | Flamm et al.                                       |   |
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|   |   | Filing Date              | 3/18/04          |
|   |   | First Named Inventor     | Doan             |
|   |   | Art Unit                 | 1765             |
|   |   | Examiner Name            | Not Yet Assigned |
| Sheet   | 2 | of                       | 6                |
|   |   | Attorney Docket Number   | P119-US          |

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|   |   |    | Art Unit                 | 1765                   |         |
|   |   |    | Examiner Name            | Not Yet Assigned       |         |
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|   |   | First Named Inventor     | Doan             |
|   |   | Group Art Unit           | 1765             |
|   |   | Examiner Name            | Not Yet Assigned |
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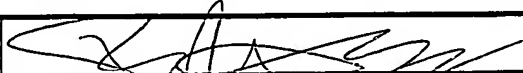
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